INFORMATION DISCLOSURE CITATION

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ATTY DOCKET NO.	SERIAL NO.
YOR920000447US2 (13796A)	Unassigned
Alessandro Callegari, et al.	
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U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
AC		5,312,565	11/01	Misra, et al.			
		6,037,003	3/14/00	Gordon, et al.			
		5,728,222	3/17/98	Barbee, et al.			
		5,648,113	7/15/97	Barbee, et al.			
		5,540,777	7/30/96	Barbee, et al.			
		5,431,734	7/11/95	Chapple-Sokol, et al.			
AC		4,097,314	6/27/78	Schlesier, et al.			

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES	TRANSLATION NO

OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

AC			Eble, R., et al., "Low Temperature Aluminum Oxide Deposition Using Trimethylaluminum", Journal of Electronic Materials, Vol. 12, No. 3, pp. 587-601 (1983);
AC			Kim, J.S., et al., "Fabrication of Aluminum Oxide Thin Films by a Low-Pressure Metalorganic Chemical Vapor Deposition Technique", App. Phys. Lett., 62(7), Feburary 15, 1993;

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[signature]	9/27/04

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AC			Fournier, J., et al., "Preparation and Characterization of Thin Films of Alumina by Metal-Organic Chemical Vapor Deposition", Mat. Res. Bull., Vol. 23, pp. 31-36, 1988;
AC			Klein, T.M., et al. "Evidence of Aluminum Silicate Formation During Chemical Vapor Deposition of Amorphous A12O3 Thin Films on Si (100)", Applied Physics Letters, Vol. 75, No. 25, pp. 4001-4003, 1999;

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AC			Lo, S.-H, et al., "Quantum-Mechanical Modelling of Electron Tunneling Current From the Inversion Layer of Ultra-Thin-Oxide nMOSFET's", IEEE Electron Device Letters, Vol. 18, No. 5, pp. 209-211, May 1997;
AC			Mutoh, H., et al., "Multilayer Metallization with Planar Interconnect Structure Utilizing CVD A12O3 Film", J. Electrochem. Soc.: SOLID-SCIENCE AND TECHNOLOGY, Vol. 12, No. 7, pp. 987-992, July 1975; and

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OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

AC			Yom, S.S., et al., "Growth of ?-A12O3 Thin Films on Silicon by Low Pressure Metal-Organic Chemical Vapour Deposition", Elsevier Sequoia, 213, pp. 72-75, 1992.

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